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Poincare maps of collisionless particles in banana orbits in rippled magnetic fields of a tokamak onto (toroidal angle, magnetic flux function) phase space. Since the fractions of open orbits increase with energy shifts from a ripple resonance at 1.5 MeV and particles which jump into island orbits by collisions enhance diffusions, the diffusion coefficient of a particles has local maxima in both sides of ripple resonance energies. (Hideyuki MIMATA *et al.*, Plasma and Fusion Research Vol.4, 008 (2009) <http://www.jspf.or.jp/PFR/>)



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